

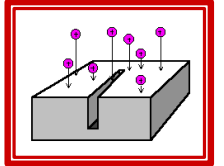
# **LOW-POWER mWAVE PLASMA SOURCE FOR MICROSYSTEMS**

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**Northeastern University  
Boston, MA  
- USA -**



# Outline



## DEVICE DESCRIPTION

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- ❖ **Low-cost** gap-excited microwave plasma source
- ❖ **Low-power** device
- ❖ **Atmospheric pressure**

## PROBE DIAGNOSTICS

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- ❖ **High-density** discharge
- ❖ Low sheath voltage

## SPECTRUM ANALYSIS

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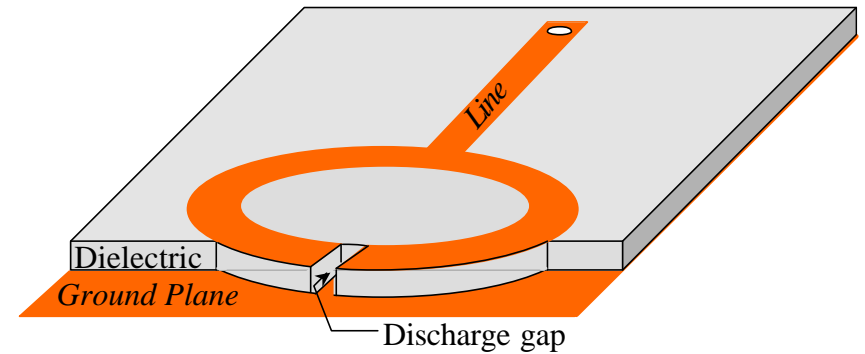
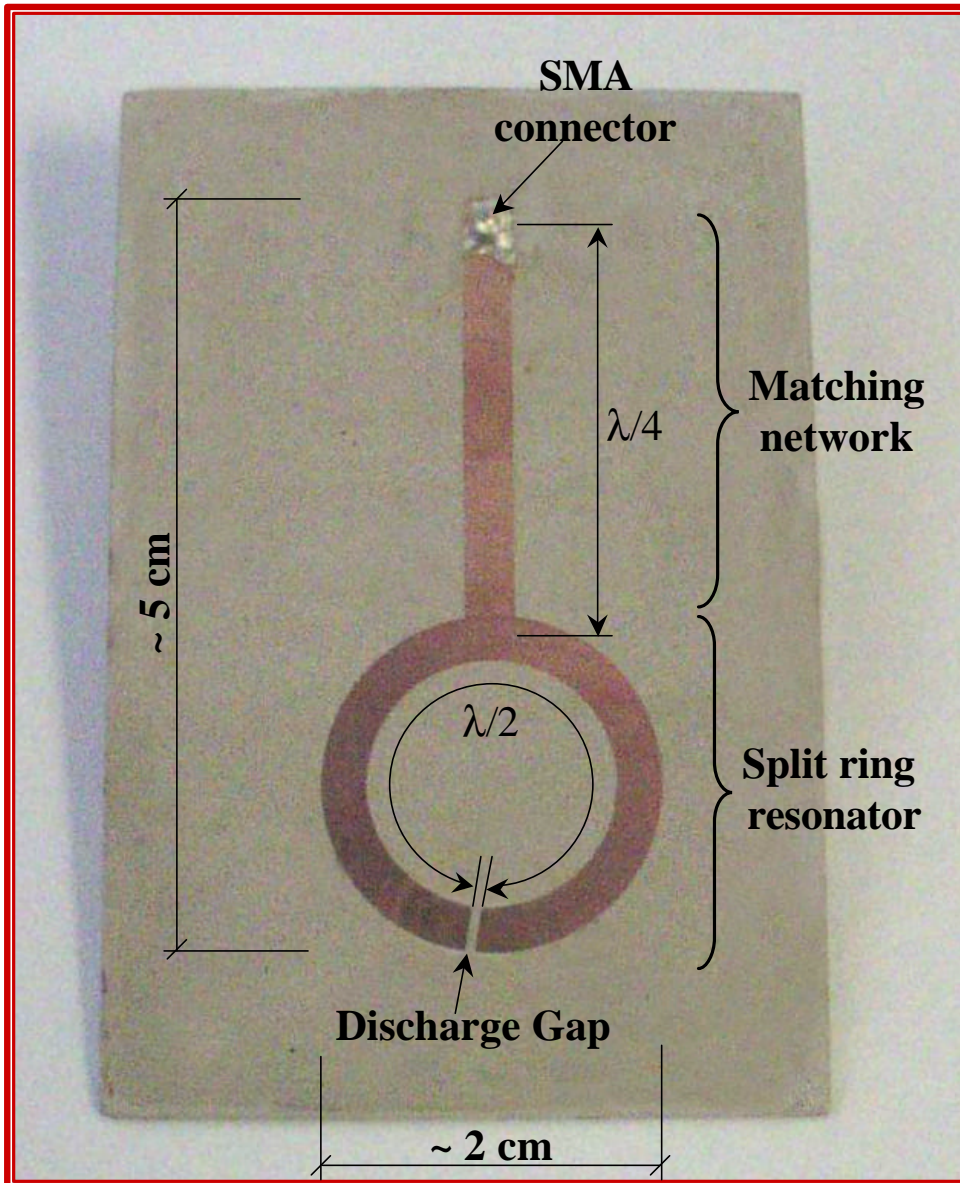
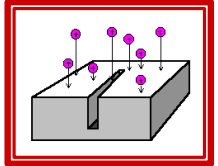
- ❖ Non-equilibrium, **low-temperature** discharge

## CONCLUSIONS

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# Plasma Source Description



## RT/Duroid 6010.8

Dielectric: Ceramic reinforced teflon  
Dielectric constant  $\epsilon_r=10.8$   
Dielectric thickness: 635 $\mu$ m

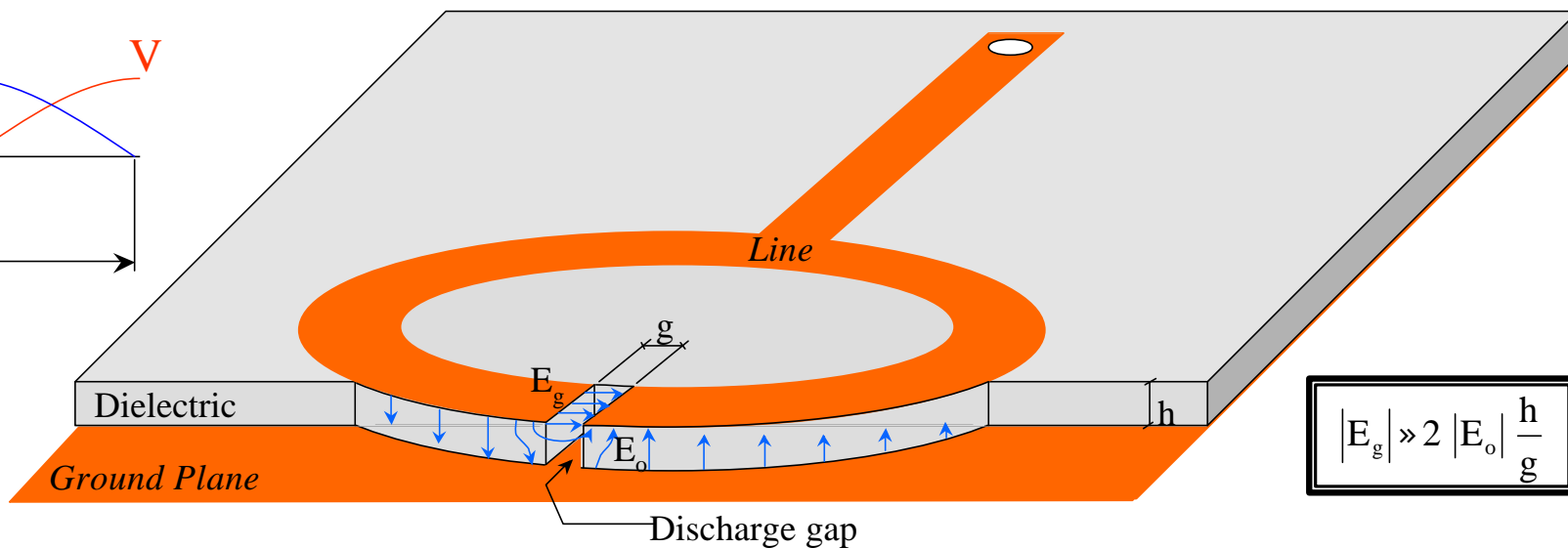
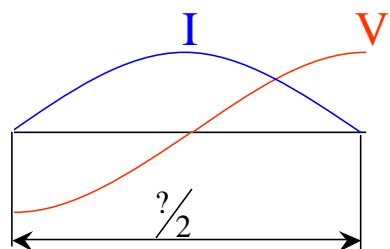
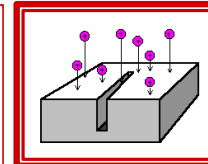
Conductor: Copper  
Conductor thickness: 9  $\mu$ m

## Operation Conditions

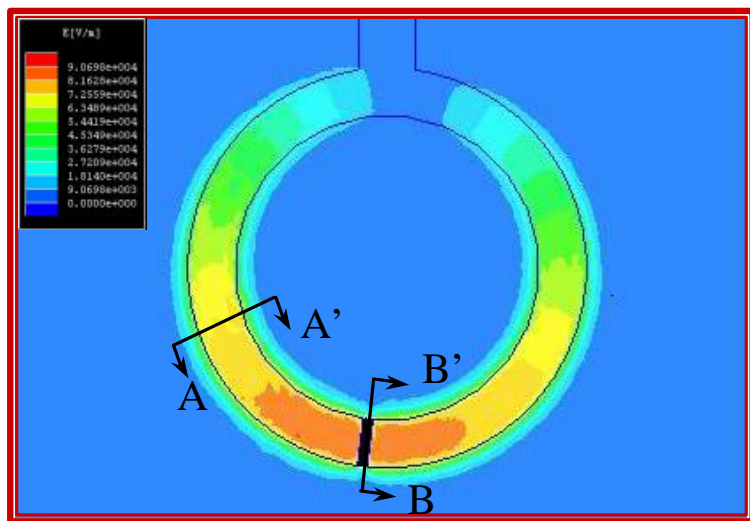
900 MHz  
0.1 - 760 torr  
0.150 - 3 W



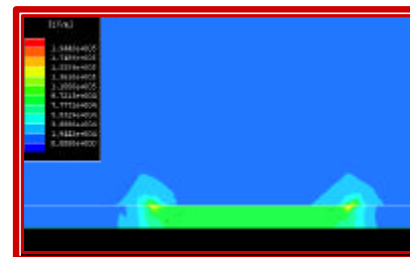
# Principle of Operation



$$|E_g| \gg 2 |E_0| \frac{h}{g}$$



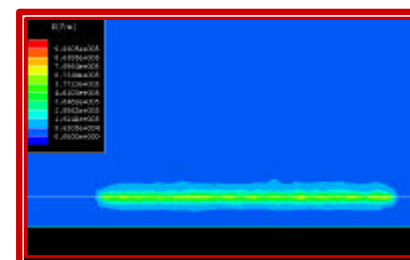
Magnitude of the electric field  $|E|$   
Simulation using HFSS from Ansoft



Section AA'

Line plane

Ground plane



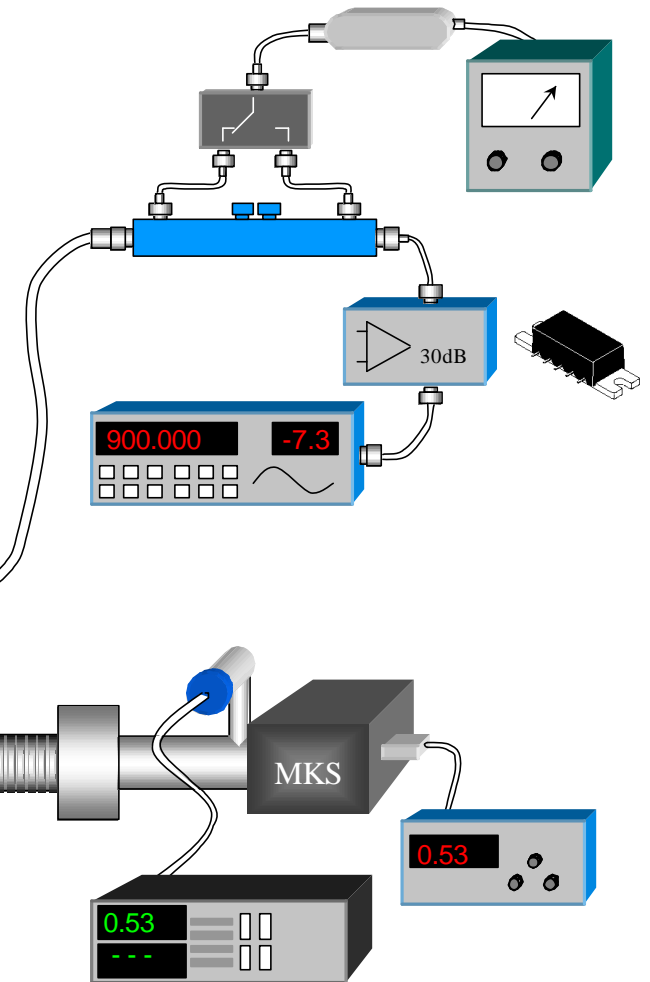
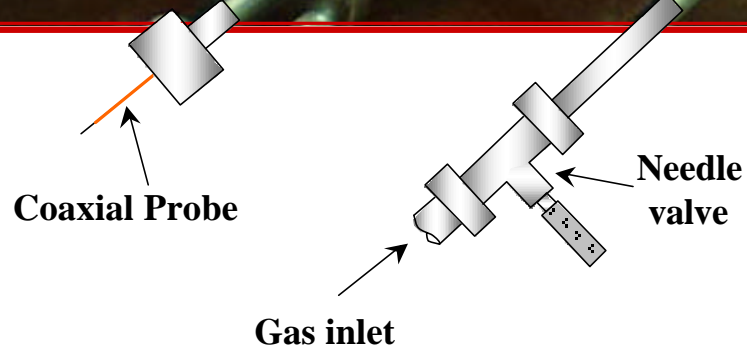
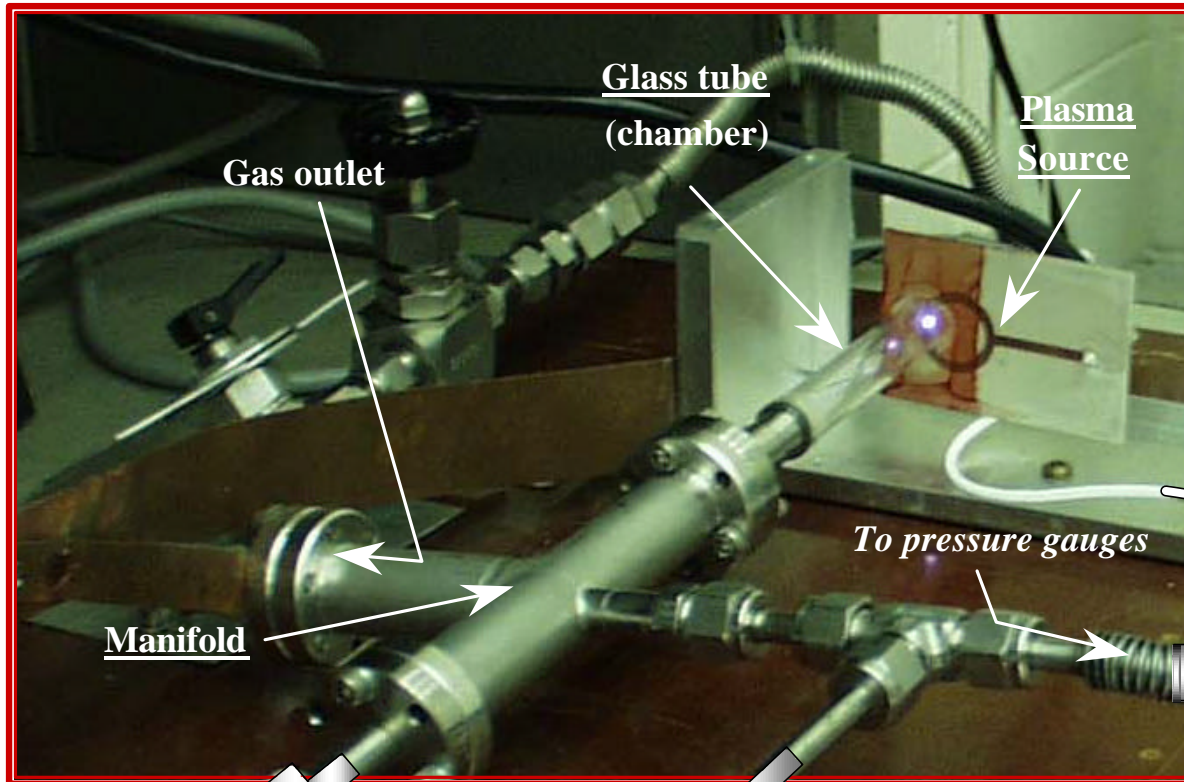
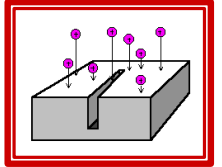
Section BB'

Line plane

Ground plane

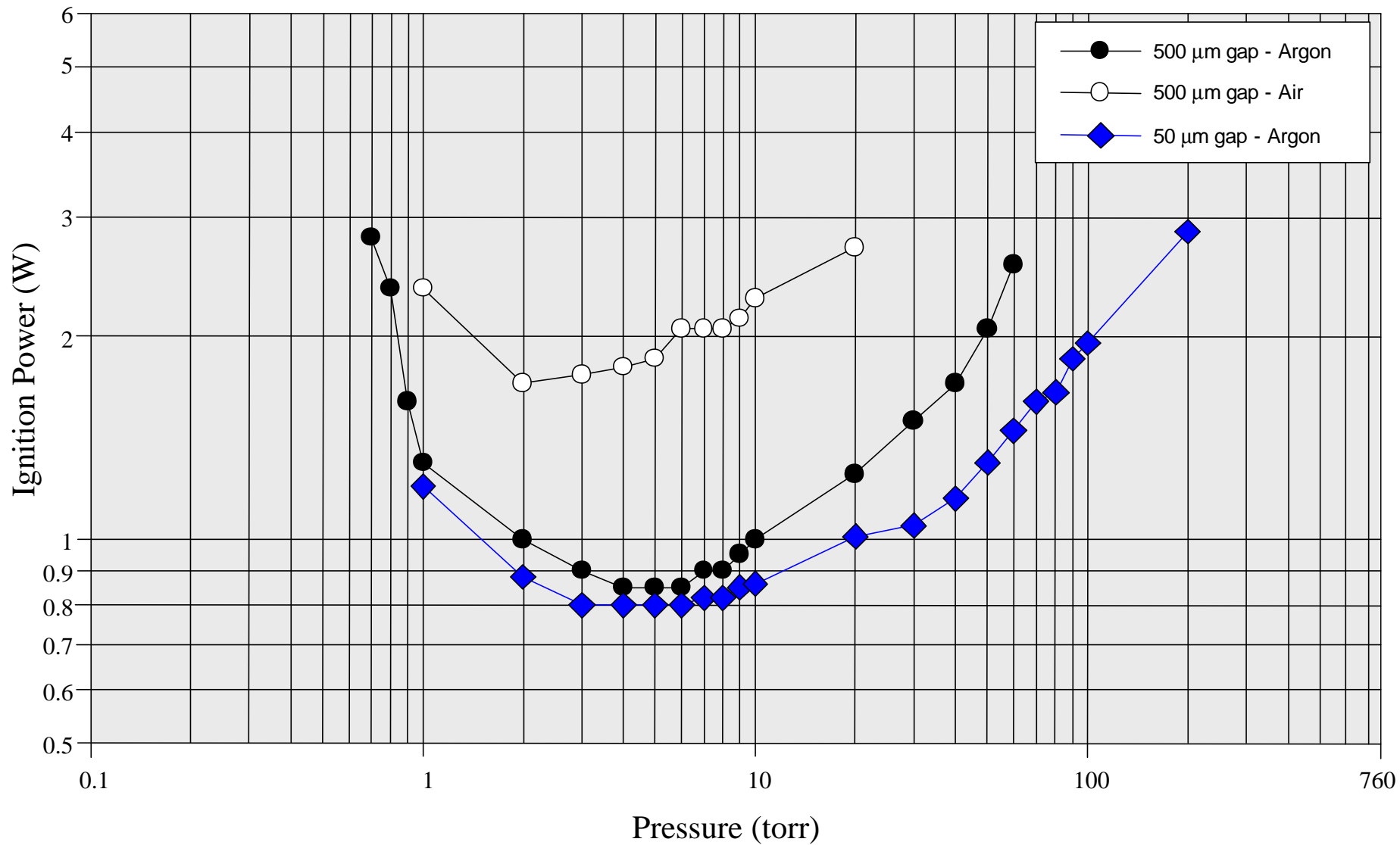
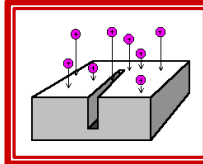


# Experiment Set-up



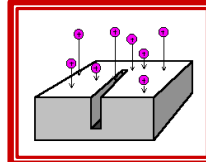


# Ignition Power & Gap engineering

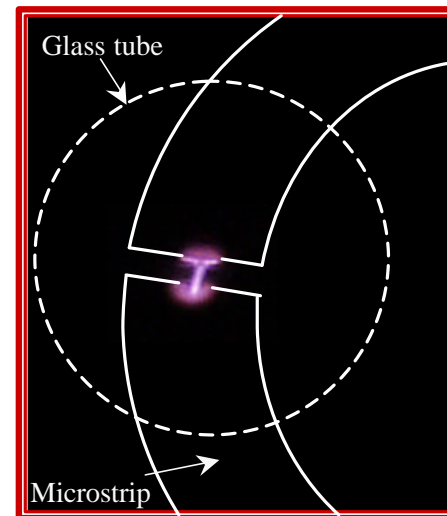
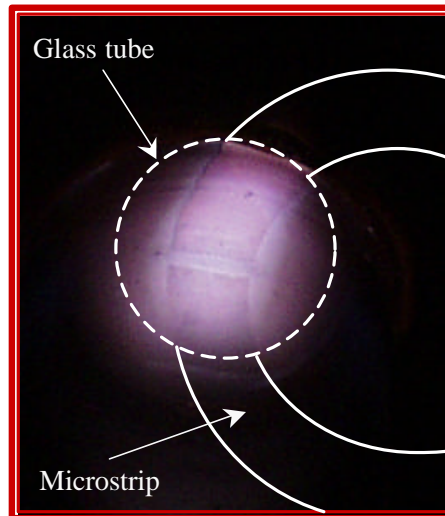
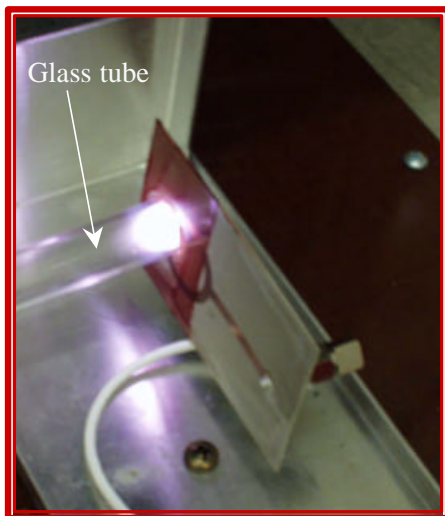
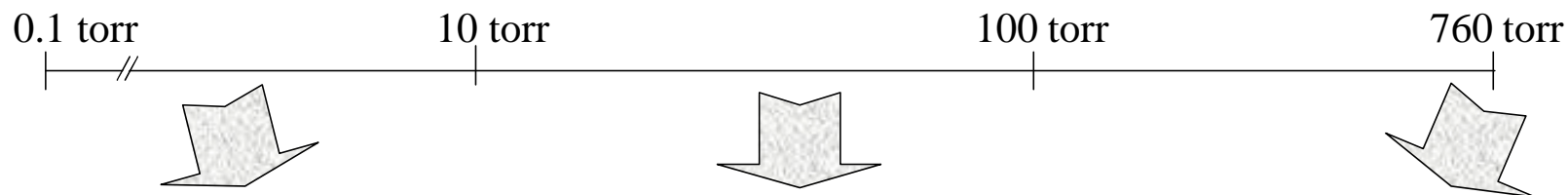




# Pressure Range of Operation



## Ar plasma @ 1W, 900 MHz



### Probe diagnostics:

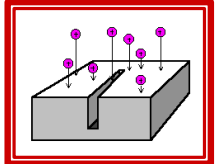
- ❖ Ion Density  $\sim 10^{11} \text{cm}^{-3}$
- ❖ Floating Potential  $< 5 \text{V}$

### Spectroscopy:

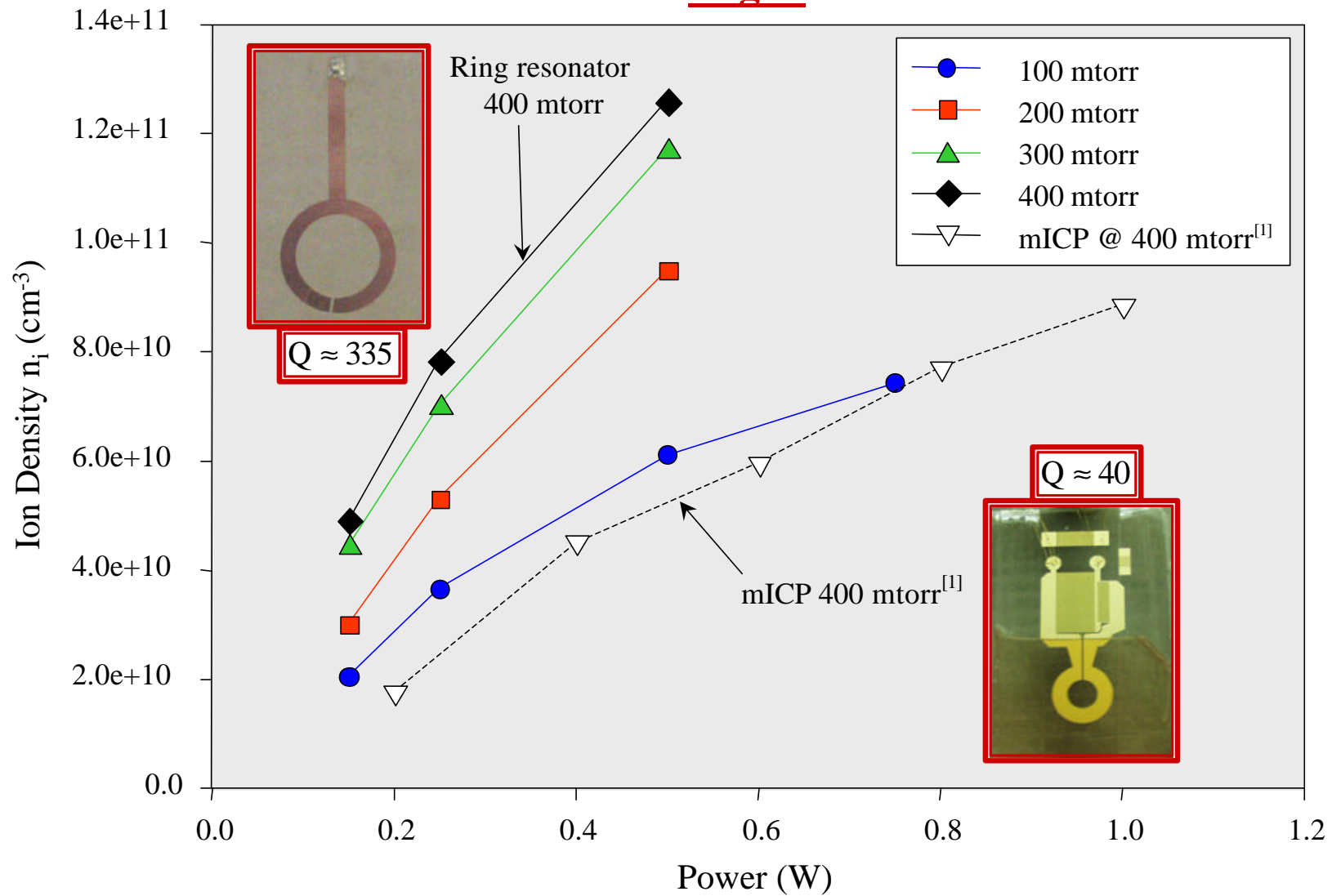
- ❖  $T_{rot} = 400 \text{K}$
- ❖  $T_{vib} = 0.7 \text{eV}$
- ❖  $T_{exc} = 0.32 \text{eV}$



# Probe diagnostics: Ion density



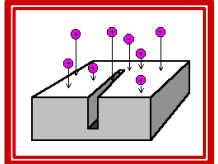
## Argon



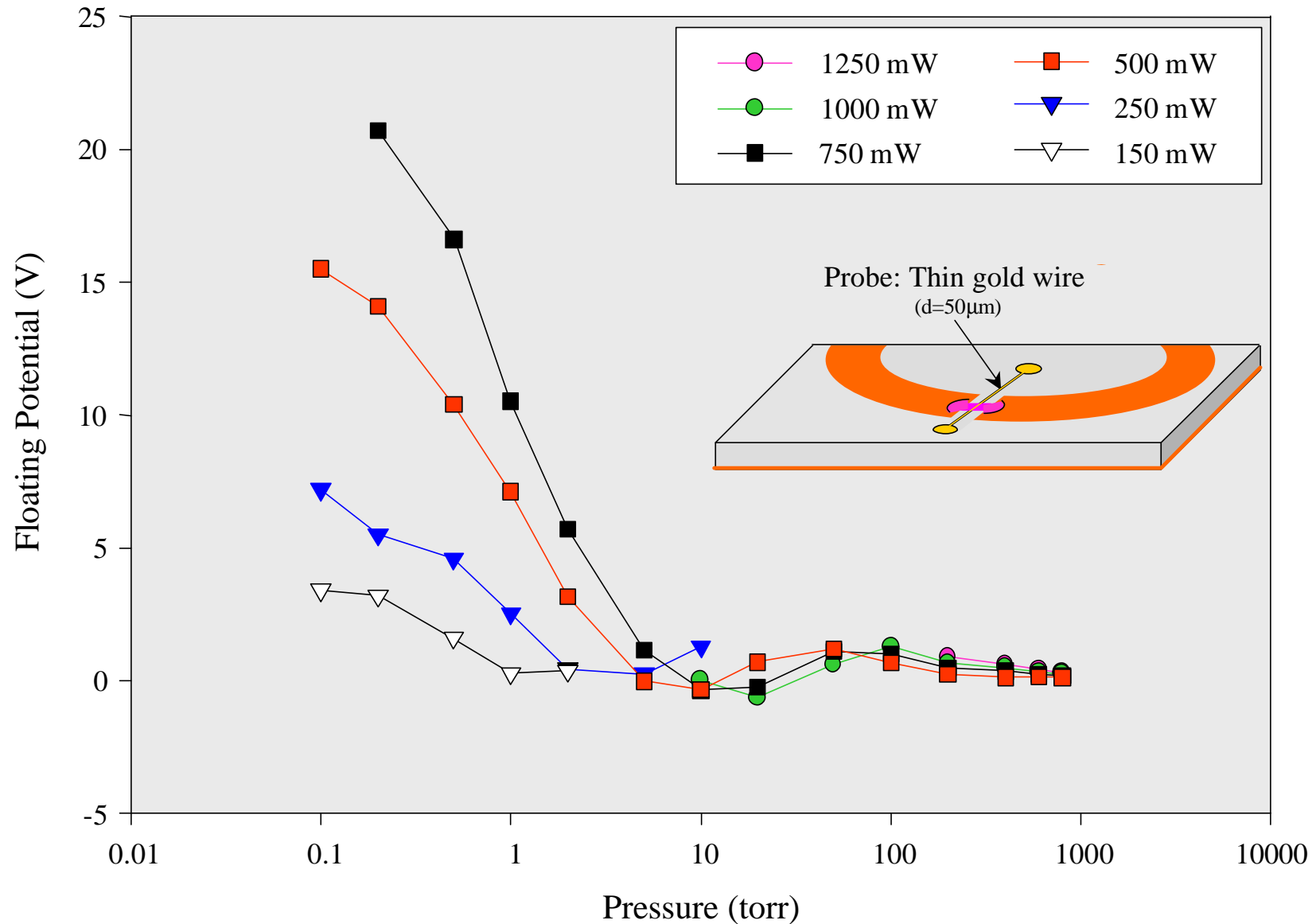
[1] Iza F. and Hopwood J., Plasma Sources Science and Technology, vol. 11, no. 3, pp. 229-235, August 2002



# Probe diagnostics: Floating Potential

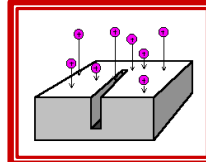


## Argon

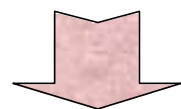
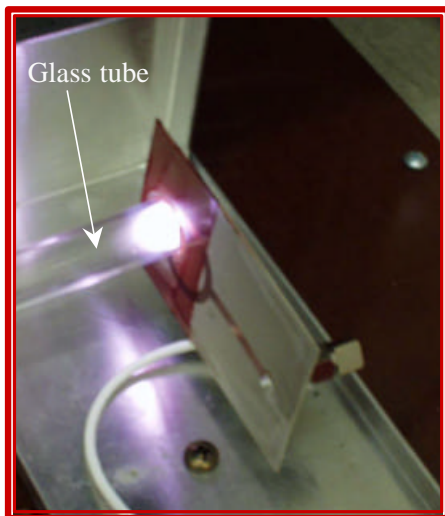
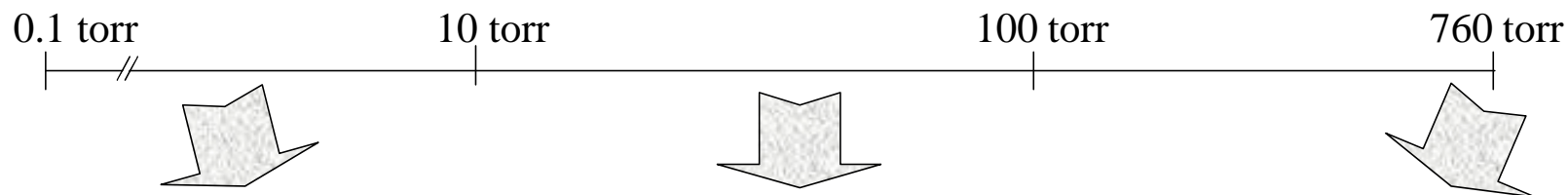




# Pressure Range of Operation

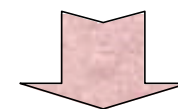
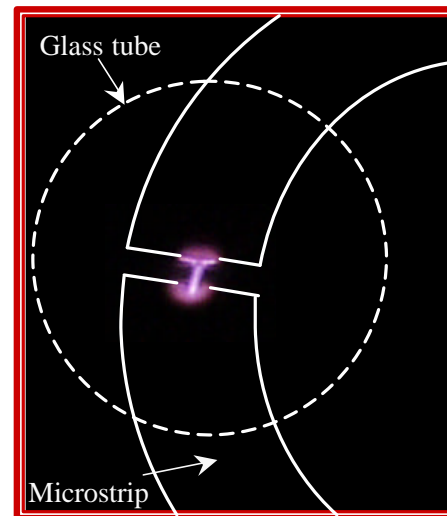
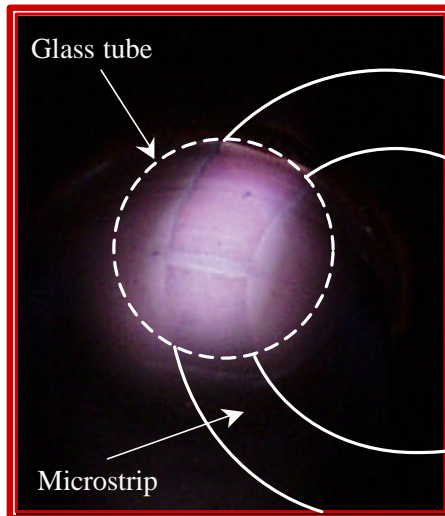


## Ar plasma @ 1W, 900 MHz



### Probe diagnostics:

- ❖ Ion Density  $\sim 10^{11} \text{cm}^{-3}$
- ❖ Floating Potential  $< 5\text{V}$

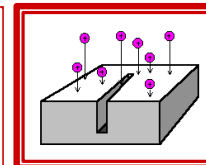


### Spectroscopy:

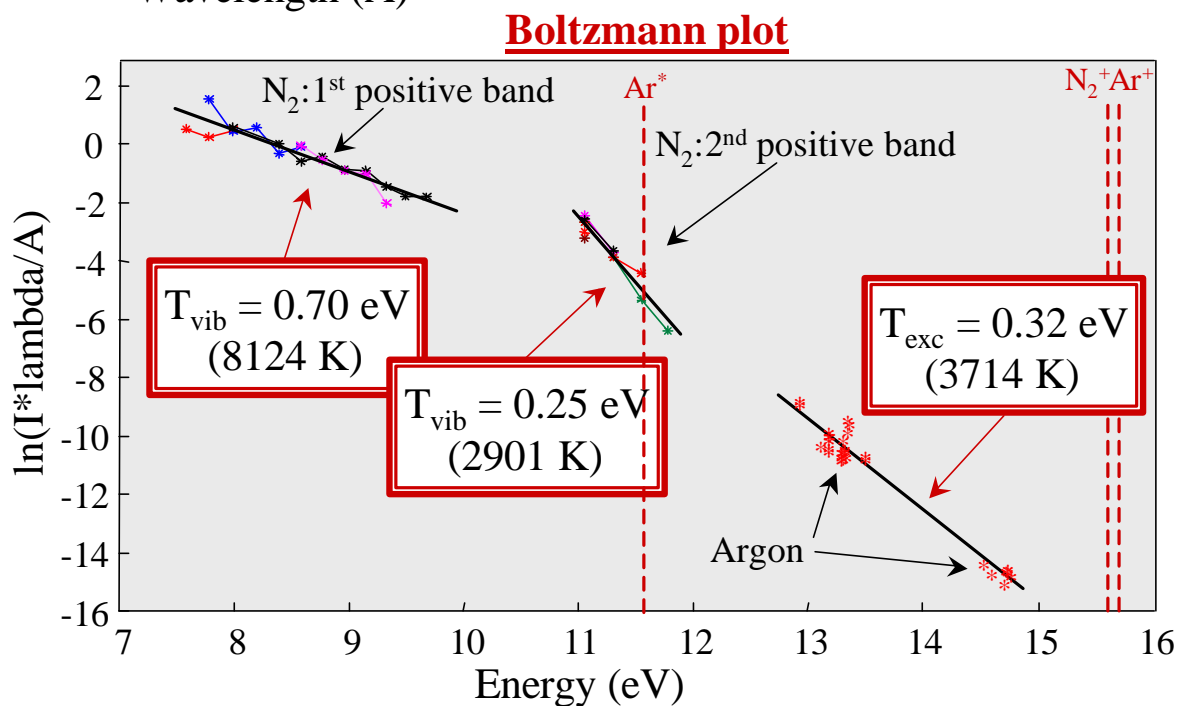
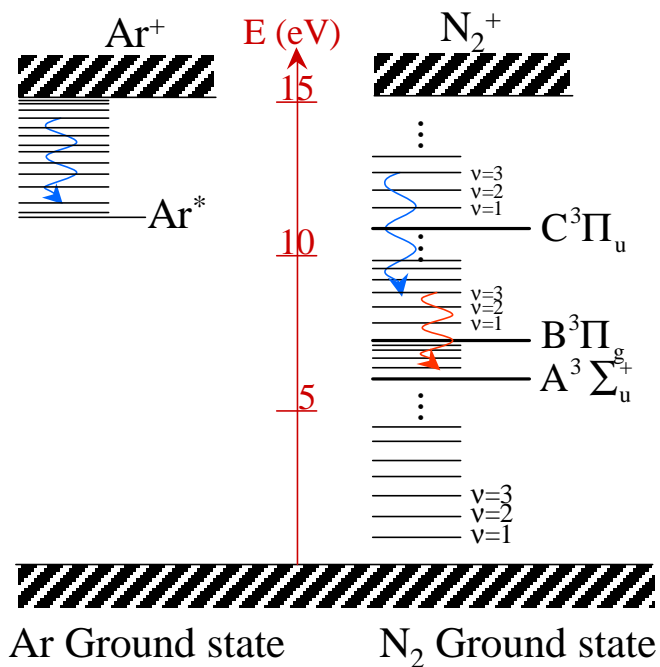
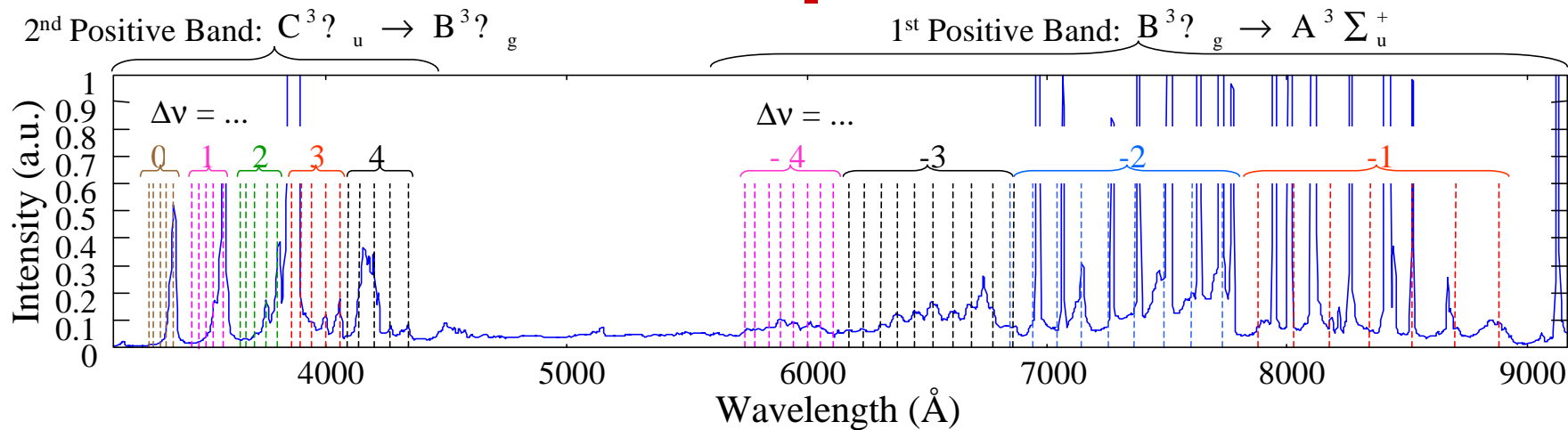
- ❖  $T_{rot} = 400\text{K}$
- ❖  $T_{vib} = 0.7\text{eV}$
- ❖  $T_{exc} = 0.32\text{eV}$



# $T_{\text{excitation}}$ and $T_{\text{vibrational}}$ @ 760 torr

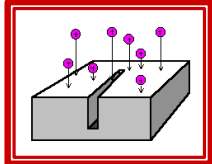


99.9% Ar + 0.1% N<sub>2</sub> : 760 torr, 1.5 W

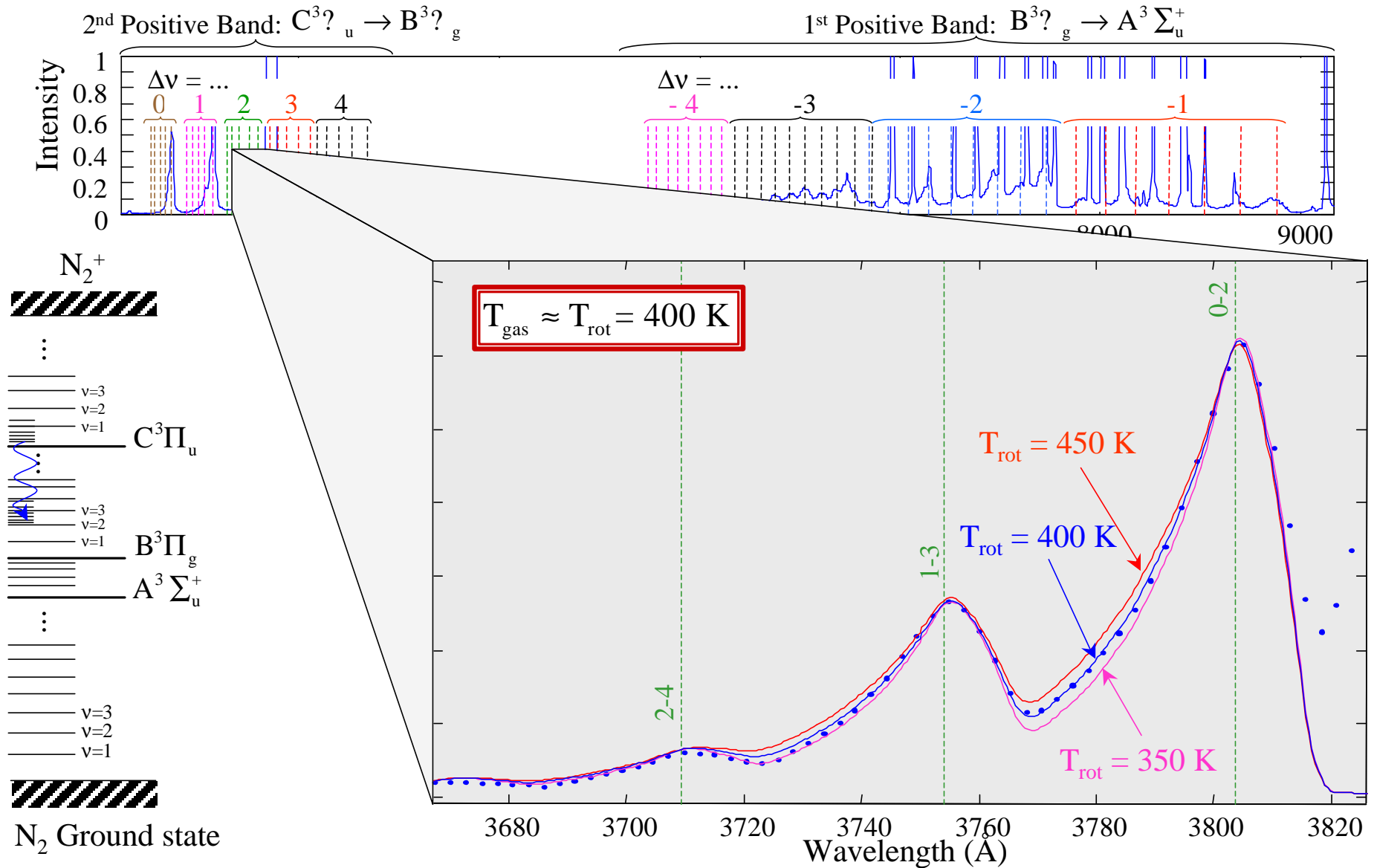




# Rotational Temperature $T_{rot}$ @760 torr

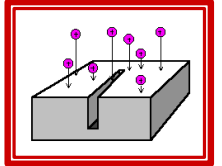


**99.9% Ar + 0.1% N<sub>2</sub> : P=760 torr, 1.5 W**



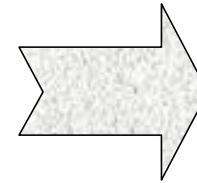


# Conclusions



## NEW DEVICE BASED ON A SPLIT-RING RESONATOR

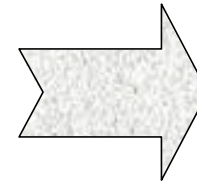
- ❖ Low cost, robust and high-Q
- ❖ Low-Power
  - 0.5W Argon @ 760torr
- ❖ Wide pressure range operation
  - 0.1-760 torr



**PORTABLE  
DEVICE**

## PROBE DIAGNOSTICS (LOW PRESSURE)

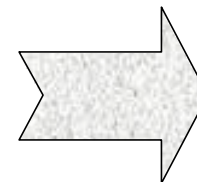
- ❖ High-density discharge
- ❖ Small sheath voltage at pressures  $> 3$  torr



**EFFICIENT AND  
DURABLE**

## SPECTRUM ANALYSIS

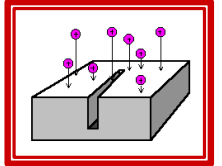
- ❖ Non-thermal plasma
- ❖ 99.9% Ar +0.1%N<sub>2</sub>, 760 torr, 1.5W
  - $T_{\text{exc}} = 0.32\text{eV}$  (3714 K)
  - $T_{\text{vib}} = 0.7\text{eV}$  (8124 K)
  - $T_{\text{rot}} = 0.03\text{eV}$  (400K)



**LOW-TEMP.  
APPLICATIONS**



# Acknowledgment



*This research has been supported by **Northeastern University**, the **Fulbright Program**, and the **National Science Foundation** under Grant No. DMI-0078406.*

